

## Current and field induced domain wall creep in Ta/CoFeB/MgO/Ta wire

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Domain wall (DW) motion in materials with perpendicular easy axis has been intensively studied in recent years because of its potential to realize fast magnetization reversal with a low current. In case that magnetic field ( $H$ ) or current ( $I$ ) much less than the threshold is applied to a DW, the DW is moved by thermal activation while interacting with the disorder in the material [1]. This sub-threshold phenomenon called “creep” has gathered considerable interest because of rich information about the mechanism for the DW motion. Since Ta/CoFeB/MgO is a promising material system for DW applications [2], we study the DW creep motion in Ta/CoFeB/MgO wires driven by both  $H$  and  $I$ .

The stack structure is Si/SiO<sub>2</sub> sub/ Ta (0.5 nm)/ CoFeB (1.2 nm)/ MgO (1.5 nm)/ Ta (1 nm). The stack is patterned into 5  $\mu\text{m}$  wide wires by photolithography and Ar ion milling. The DW motion is observed by magneto-optic Kerr effect (MOKE) microscope after applying  $H$  or  $I$  pulses.

Figure 1 shows the DW velocity ( $v$ ) vs. applied current density ( $J$ ) or  $H$ . The non-linearity of the curve implies that the motion is in the creep regime. In the creep regime,  $v$  follows a scaling relation with respect to the  $H$  or  $I$ :  $v = v_0 \exp \left[ -\frac{U}{kT} \left( \frac{f_c}{f} \right)^\mu \right]$ , where  $U$  is the energy barrier,  $f$  is the applied  $H$  or  $I$  and  $f_c$  is their critical value. The exponent  $\mu$  reflects the mechanism of DW motion [3,4]. From the fitting shown in the insets in Fig. 1,  $\mu$  is determined to be  $\sim 0.27$  for the  $H$  driven case while it is  $\sim 0.6$  for the  $I$  driven case. This is the first report of different  $\mu$  for the  $H$  and the  $I$  driven case observed for a metallic system. The result can possibly be interpreted in terms of the nature of the disorder and the torque acting on the DW.

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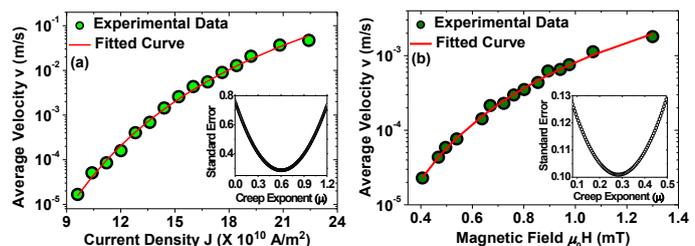


Fig. 1: DW velocity ( $v$ ) as a function of current density (a) and magnetic field (b). Insets show standard error curve for determination of creep exponent.